A split algorithm of manufacturing stencil mask and dividing pattern for making holographic optical elements (Withdrawal Notice)

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Proc. SPIE 10818, 108181E (2018)

Online Publication Date: 2 November 2018 Withdrawn from Publication: 4 February 2019

Conference Date: 11 October-13 October 2018

Conference Location: Beijing, China

Conference Title: Holography, Diffractive Optics, and Applications VIII Conference Chairs: Yunlong Sheng, Chongxiu Yu, Changhe Zhou

Publisher's Note: This manuscript, originally published on 2 November 2018, has been withdrawn by the publisher for editorial reasons.